

WHAT IS CLAIMED IS:

Sub C1 > 1. A semiconductor device having a plurality of wirings juxtaposed with one another and a SiOF insulating film being in
5 contact with the wirings, characterized in that the fluorine concentration of the SiOF insulating film at a wiring gap portion is set to be higher than the fluorine concentration of the SiOF insulating film on the wirings.

10 2. The semiconductor device as claimed in claim 1, wherein the SiOF insulating film at a wiring gap portion comprises a first SiOF film and a second SiOF film formed on the first SiOF film, the SiOF insulating film on the wirings
15 comprises the second SiOF film, and the fluorine concentration of the first SiOF film is higher than the fluorine concentration of the second SiOF film.

Sub C2 > 3. The semiconductor device as claimed in claim 2, wherein the thickness of the first SiOF film at a center of the
20 wiring gap portion is within the range of 1/3 to 1/1 times of the thickness of the wirings.

Sub 07 4. The semiconductor device as claimed in claim 1, wherein the fluorine concentration of the first SiOF film is set
25 to 5 atom % or more, and the fluorine concentration of the second SiOF film is set to be less than 5 atom %.

Sub C3 > 5. A semiconductor device having a plurality of wiring layers each having a plurality of wirings juxtaposed with one
30 another and a SiOF interlayer insulating film, characterized in

05863737 0586304

C3
Cmt.

that the fluorine concentration of the SiOF interlayer insulating film at a wiring gap portion is set to be higher than the fluorine concentration of the SiOF interlayer insulating film on the wirings.

5

6. The semiconductor device as claimed in claim 5, wherein the SiOF interlayer insulating film at a wiring gap portion comprises a first SiOF film and a second SiOF film formed on the first SiOF film, the SiOF interlayer insulating film on the wirings comprises the second SiOF film, and the fluorine concentration of the first SiOF film is higher than the fluorine concentration of the second SiOF film.

Sub 047

15 7. The semiconductor device as claimed in claim 6, wherein the thickness of the first SiOF film at a center of the wiring gap portion is within the range of 1/3 to 1/1 times of the thickness of the wirings.

Sub 07

20 8. The semiconductor device as claimed in claim 6, wherein the fluorine concentration of the first SiOF film is set to 5 atom % or more, and the fluorine concentration of the second SiOF film is set to be less than 5 atom %.

25 9. A semiconductor device manufacturing method, comprising:

a step of forming a plurality of wirings on the same plane;

a step of forming a first insulating film of SiOF on the plane having the wirings formed thereon and removing the first
30 insulating film on the upper surface of the wirings;

a step of introducing fluorine into the first insulating film remaining at a wiring gap portion; and

a step of forming a second insulating film of SiOF.

5 10. The semiconductor device manufacturing method as claimed in claim 9, wherein the fluorine concentration of SiOF of the second insulating film is set to be equal to or less than the fluorine concentration of SiOF of the first insulating film before fluorine introduced.

10

11. The semiconductor device manufacturing method as claimed in claim 9, wherein fluorine is introduced by ion implantation under the condition of an acceleration energy of 10 keV to 100 keV and a dose amount of $5 \times 10^{14} \text{ cm}^{-2}$ to
15 $3 \times 10^{15} \text{ cm}^{-2}$.

12. A semiconductor device manufacturing method, comprising:

20 a step of forming a plurality of wirings on the same plane;

a step of forming a first insulating film of SiOF on the plane having the wirings formed thereon and introducing fluorine into the first insulating film;

25 a step of removing the first insulating film on the upper surface of the wirings; and

a step of forming a second insulating film of SiOF.

13. The semiconductor device manufacturing method as claimed in claim 12, wherein the fluorine concentration of SiOF of
30 the second insulating film is set to be equal to or less than the

0966373 0966304

fluorine concentration of SiOF of the first insulating film before fluorine introduced.

14. The semiconductor device manufacturing method as
5 claimed in claim 12, wherein fluorine is introduced by ion
implantation under the condition of an acceleration energy of
10 keV to 100 keV and a dose amount of $5 \times 10^{14} \text{ cm}^{-2}$ to
3 $\times 10^{15} \text{ cm}^{-2}$.

10

15

20

25

30

05863737-052304
T052000-2575950